| Ref # | Hits | Search Query | DBs | Default Operator | Plurals | Time Stamp |
|----------|-------|--|---|---------------------|---------|------------------|
| L1 | 2 | "5499282".pn. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR . | OFF | 2005/09/21 10:21 |
| L2 | 5947 | ("355"/\$.ccls. or "250"/\$.ccls. or "378"/\$.ccls.) and (debrib or particle or dust or contamin\$4) near9 (prevent\$4 or discharg\$4 or avoid\$4 or collect\$4) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/09/21 10:23 |
| L3 | 1881 | 2 and (voltage) and (cathode or electrode or anode) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR . | ON | 2005/09/21 10:23 |
| L4 | 1481 | 3 and ((electric adj3 (field or region or area)) between near8 (radiation or light or beam or ray)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/09/21 10:27 |
| L5 | 600 | 3 and (((electric adj3 (field or region or area)) between near8 (radiation or light or beam or ray)) near5 (electrode)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON . | 2005/09/21 10:27 |
| L6 | 152 | 5 and (((reticle or mask) and (substrate or wafer)) or \$4lithograph\$4 or ((exposure) adj3 (apparatus or device or system))) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR . | ON | 2005/09/21 10:29 |
| L7 | 138 | 6 and (projection or lens or optical) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/09/21 10:30 |
| L8 | 74312 | 7 (gas near5 electrode) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/09/21 10:33 |
| L9 | 25 | 7 and (gas near5 electrode) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/09/21 10:33 |